

1 TANTALUM SPUTTERING TARGET AND METHOD OF MANUFACTURE

ABSTRACT OF THE DISCLOSURE

5 Described is a method for producing high purity tantalum, the high purity tantalum  
so produced and sputtering targets of high purity tantalum. The method involves purifying  
starting materials followed by subsequent refining into high purity tantalum.

10 BJE IRV20432.1.-5/21/99 11:13 am

15  
20  
25  
30  
35

